

Applicant: Donald G. Parent
For: SYSTEM FOR COATING INSULATIVE SUBSTRATES

ABSTRACT OF THE DISCLOSURE

5 A system for a method of applying a coating to an insulative substrate. The method
includes applying a coating material to the insulative substrate by physical vapor
deposition to a predetermined thickness at a rate and for a predetermined time which does
not cause thermal damage to the insulative substrate. Then, before thermal damage can
occur, moving the partially coated substrate proximate and active cooling station device
10 to drive the temperature of the insulative substrate substantially down. The deposition
and cooling steps are then repeated until the desired coating thickness is obtained to avoid
thermal damage to the substrate.